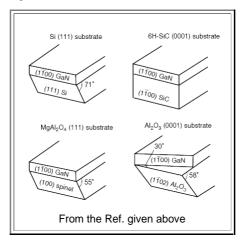
## **Cleaving Semiconductors for (Blue) Lasers Diodes**

- The module is based on the paper of Kuramta et al: in FUJITSU Sci. Tech. J. **342** (1998). p.191. The authors provide data about **cleavage planes in semiconductors**.
  - The preferred cleavage planes of a semiconductor are not as clear-cut as it seems. As everybody know who just once dropped a {100} Si wafer knows, the fracture plans are the {110} planes; a large part of the literature, however, including the paper given above, insists that it should be {111}.
  - Be that as it may, here we take the planes given in the article.

| Material                       | Crystal structure | Effective lattice<br>mismatch (%) | Difference in thermal<br>expansion coefficient (×10-6) | Cleavage | Stability |
|--------------------------------|-------------------|-----------------------------------|--|----------|-----------|
| Si                             | Diamond           | 20.1                              | -2.0   | (111)    | Good      |
| GaAs                           | Zinc blende       | 25.3                              | 0.4  | (110)    | Fair      |
| GaP                            | Zinc blende       | 20.7                              | -0.9   | (110)    | Fair      |
| MgO                            | Rock salt         | -6.5                              | 4.9  | (100)    | Fair      |
| MnO                            | Rock salt         | -1.4                              |  | (100)    | Bad       |
| CoO                            | Rock salt         | -5.4                              |  | (100)    | Bad       |
| NiO                            | Rock salt         | -7.6                              |  | (100)    | Bad       |
| MgAl₂O₄                        | Spinel            | -10.3                             | 1.9  | (100)    | Good      |
| NdGaO₃                         | Perovskite        | -1.2                              | 1.9  |          | Fair      |
| ZnO                            | Wurtzite          | 2.0                               | -2.7   | (1-100)  | Fair      |
|                                |                   |                                   |  | (11-20)  |           |
|                                |                   |                                   |  | (0001)   |           |
| 6H-SIC                         | ZnS 6H            | -3.4                              | -1.4   | (1-100)  | Good      |
|                                |                   |                                   |  | (11-20)  |           |
|                                |                   |                                   |  | (0001)   |           |
| LiAIO <sub>2</sub>             | β-NaFeO₂          | 1.7                               | 1.7  | (001)    | Fair      |
| LiGaO <sub>2</sub>             | β-NaFeO₂          | -0.1                              | 1.9  | (010)    | Fair      |
| Al <sub>2</sub> O <sub>3</sub> | Corundum          | -13.8                             | 1.9  | (1-102)  | Good      |
| LiNbO₃                         | Ilmenite          | -6.7                              | 9.9  | (1-102)  | Bad       |
| LiTaO₃                         | Ilmenite          | -6.8                              | 10.6   | (1-102)  | Fair      |
|                                |                   |                                   |  |          |           |
|                                |                   | From the I                        | Ref. given above                                       |          |           |

- GaN as a semiconductor technology material only comes as a thin layer on a substrate other than GaN since there simply are no usable GaN single crystals
  - As we know, if we grow thin layers with different lattices, we have to watch out for <u>misfit dislocations</u>. It is important to look for substrates with a lattice constant as similar as possible to that of the thin layer to be grown. The table above shows the lattice mismatch of prospective substrates to **GaN** and thus gives a guideline.
- If we want to make a Laser diode form the thin film, we have a few more requirements besides "just" avoiding misfit dislocations as best as we can:
  - The substrate should have a high electrical and thermal conductivity. The first property would make it easier to supply the large current densities we need to operate a Laser diode, the second to remove efficiently the heat generated during operation.
  - The whole stack of substrate and layers should cleave nicely on a well-defined and very flat plane because the two relevant surfaces obtained by cleavage will serve as the mirrors of the <a href="Faby-Perot resonator">Faby-Perot resonator</a> we need for a Laser. Now look at the possible cleavage relations:



Summing up: There is no ideal substrate - you have to find the optimal compromise once more if you wan to make the blue Laser diode.